NEGATIVE PHOTOSENSITIVE COMPOSITION

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Abstract

PROBLEM TO BE SOLVED: To provide excellent contrast between an exposed part and a non- exposed part in relation to a near infrared ray area, and to enable the sufficient residual film ratio of an image part by including an alkali soluble organic polymer material and azide compound of a cyanine dye.
SOLUTION: This composition contains an alkali soluble organic polymer material having a phenol hydroxyl group and the azide compound of a cyanine dye having near infrared ray absorbing ability. As an alkali soluble organic polymer material having phenol hydroxyl group, a novolac resin, resole resin, polyvinyl phenol resin and a copolymer of an acrylic acid derivative having phenolic hydroxyl group is used. As the azide compound of the cyanine dye having the near infrared ray absorbing ability, an azide compound of cyanine dye obtained by bonding a heterocyclic group containing nitrogen atom, oxygen atom, or sulfur atom with polymethine (-CH=), for example, an azide compound of various dyes is used, such as a quinoline-based or an indole-based dye of a cyanine dye in a wide sense.

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